

L Number	Hits	Search Text	DB	Time stamp
2	4486	(250/310,311,309,492.22).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:10
3	43356	(SEM or (scanning adj electron adj microscope))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:11
4	30513	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:07
5	11020	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:12
6	200	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:14
7	37	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist)) and ((edge near width) or (pattern near width))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:15
8	18	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist)) and ((edge near width) or (pattern near width)) and calculat\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:15
9	0	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist)) and ((edge near width) or (pattern near width)) and diminsion\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:16
10	29	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist)) and ((edge near width) or (pattern near width)) and characteristic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:18
11	29	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist)) and ((edge near width) or (pattern near width)) and characteristic) and pattern	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:18
12	7	((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist)) and ((edge near width) or (pattern near width)) and characteristic) and pattern) and model	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 13:19

13	5	(((((SEM or (scanning adj electron adj microscope))) and (observ\$6 or monitor\$4)) and exposure) and ((obtain\$4 or detect\$5) with imag\$5 with (resist or photoresist))) and ((edge near width) or (pattern near width))) and characteristic) and pattern) and model) and (correct\$4 with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:35
14	1909	((observ\$6 or monitor\$4) near4 process\$4) and ((critical\$4 or characteristic) near4 dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:09
15	316	((observ\$6 or monitor\$4) near4 process\$4) and ((critical\$4 or characteristic) near4 dimension\$4)) and ((SEM or (scanning adj electron adj microscope)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:10
16	119	((observ\$6 or monitor\$4) near4 process\$4) and ((critical\$4 or characteristic) near4 dimension\$4)) and ((SEM or (scanning adj electron adj microscope))) and (imag\$4 with (resist or photoresist))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:11
17	17	"117" and ((edge or pattern) near4 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:12
18	6	("117" and ((edge or pattern) near4 width)) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:13
19	5	("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:13
21	4	((("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4) and pattern\$4) and calculat\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:16
22	1	((("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4) and pattern\$4) and calculat\$5) and (ion or electron or charged-particle or (charged adj particle))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:16
20	5	((("117" and ((edge or pattern) near4 width)) and exposure) and correct\$4) and pattern\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:22
24	1873	(process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:37
25	807	((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:38
26	198	((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:39

27	139	(((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:40
28	136	(((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:41
29	43	(((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:42
30	42	((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:43
31	41	((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:44
32	41	((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:44
33	21	((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)) and (correct\$4 with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:45
34	15	((((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)) and (correct\$4 with exposure)) and (monitor\$4 near2 process\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:45

35	9	(((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)) and (correct\$4 with exposure)) and (monitor\$4 near2 process\$4)) and lithograph\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:53
36	2	(((((process\$4 with monitor\$4) and (SEM or (scanning adj electron adj microscop\$1))) and exposure) and ((critical\$4 or characteristic\$4) near dimension\$4)) and correct\$4) and ((charged adj particle) or electron)) and ((pattern or edge) near width)) and (calculat\$5 or comput\$4)) and focus\$4) and (model\$4 or referenc\$4)) and (correct\$4 with exposure)) and (monitor\$4 near2 process\$4)) and lithograph\$4) and ((250/310,311,309,492.22).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/17 14:53